



a recipe selection method based on a trim amount

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### [APPLICATION] Method of operating a system for chemical oxide removal

US Pat. 10736983 - Filed Dec 17, 2003 - Tokyo Electron Limited

For example, a simple bin algorithm can be a control **recipe selection method** that is **based on trim etch amount**. If the selected control **recipe** settings are

...

### [APPLICATION] Formula-based run-to-run control

US Pat. 10890410 - Filed Jul 14, 2004 - Tokyo Electron Limited, International Business Machines Corporation

For example, one process can comprise determining a **trim amount**, ... can use an algorithm (a Control **Recipe selection method**) **based on trim etch amount**. ...

### [APPLICATION] Method and system for realtime CD microloading control

US Pat. 10464479 - Filed Jun 18, 2003

The **trim** and etch **recipe selection** is **based** on algorithms and/or equations ... such that the isolated and dense patterns are not **trimmed** by the same **amount**; ...

...

### Feature dimension deviation correction system, method and program product

US Pat. 7289864 - Filed Jul 12, 2004 - International Business Machines Corporation, Tokyo Electron Limited

Currently IMs are typically optically (scatterometry) **based** tools. .... a process model converts a **trim amount** to a process **recipe** parameter set (for ...

### Method and system for line-dimension control of an etch process

US Pat. 7291285 - Filed May 10, 2005 - International Business Machines Corporation

In step 265 an etch time for the mask **trim** etch process is calculated **based** on the ... over a range **based** upon said value of WT1; Tjj^,=said total **amount** of

...

### Method of using a wafer-thickness-dependant profile library

US Pat. 7571074 - Filed Jan 30, 2007 - Tokyo Electron Limited

... 5 tune, and/or optimize a measurement **recipe** and/or library **selection**, ... value can be fed forward **based** on pre-etch measurements and etch **trim amount**. ...

...

### Is/nested control for soft mask processing

US Pat. 7328418 - Filed Feb 1, 2005 - Tokyo Electron Limited

Formula- **based** models can comprise equations that contain the piece- 65 wise associations of desired results with **recipe** variables **based** on some evaluated

...

### [APPLICATION] Method of Using a Wafer-Temperature-Dependant Profile Library

US Pat. 11668654 - Filed Jan 30, 2007 - TOKYO ELECTRON LIMITED

When a newly tuned and/or optimized measurement **recipe**, profile, ... value can be fed forward **based** on pre-etch measurements and etch **trim amount**. ...

Wafer-to-wafer control using virtual modules

US Pat. 7212878 - Filed Aug 27, 2004 - Tokyo Electron Limited, International Business Machines Corporation

The desired process result may comprise a **trim amount**, an etch **amount**, ... The WM control strategy **selection** and initiation can be context-based. ...

Methodology for repeatable post etch CD in a production tool

US Pat. 6858361 - Filed Sep 9, 2002

The **method** of claim 3, an **amount** of photoresist **trimmed** varies nonlinearly ... comprising choosing an etch **recipe** for the etch process **based** on the measured

...

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